



### Aktuelles Experiment:

noname.rcp

## Modellbeschreibung

Number	Layer Name	Thickness [nm]	Refr. Index	Fitted
			[632.8 nm]	
0	Air	-	1.000	no
1	NoName0	137.59	3.010	yes
2	Silicon DUV-NIR -		3.874	no

### Fit parameter

Fit parameter		Fit result
[1,1] NoName0: Thickness [	[nm]	137.59

### All parameter

Parameter [1] Wavelength [nm] [1] Angle [°] [1] Time [s] [1] Temperature [°C] [1] Sample rotation [°] [1] Depol. D0 [1] Depol. D1 [1] Depol. D2 [1] Beam diameter [1] Aperture diameter [1,1] Thickness variation [1] Wavelength resolution (nm) [1] Angle variation [1] Angle offset [°] [1] Wavelength Complete (nm) [1] Wavelength Linear [1] Fraction Overlayer [1] Backside Factor Air: Refr. index Air: Absorption	Value 632.8 70.00 0.0 23.5 0.00 1.0000 4.00 4.00 4.00 10.0 0.00 1.0000 1.000 1.000 1.000 1.000 0.000 0.000 0.000 0.000 1.000 0.000 0.000
Air: Absorption Air: N Offset	0.000 0.00000
Air: K Offset	0.00000



[1,1] NoName0: Thickness [nm]	137.59
NoName0: N0	3.000
NoName0: N1	40.0
NoName0: N2	0.0
NoName0: K0	0.000
NoName0: K1	0.000
NoName0: K2	0.000
NoName0: N Offset	0.00000
NoName0: K Offset	0.00000
Silicon DUV-NIR: N Offset	0.00000
Silicon DUV-NIR: K Offset	0.00000
Pola.Pos.	45.00
Pola.Offs.	0.00
Ret.Axis	0.00
Ret.Phase	90.00
Eta	1.00000
Ana.Offs.	0.00
Ana.Offs.Lin.	0.00
Ana.Offs.Quadr.	0.00
Psi Offs.	0.00
Psi Lin.	0.00
Psi Quadr.	0.00
Delta Offs.	0.00
Delta Lin.	0.00
Delta Quadr.	0.00
MCE	EO 7000110

59.78801488 MSE

# Measured Data

RRM001-045 / Psi, Delta / Spectral range: 300.2 nm - 1050.0 nm / Angle of incidence: 60.00  $^{\circ}$  / 9/17/2019 2:54:54 PM



